

## OXFORD ICP RIE CL -BASED 418499

 Villach

### BRIEF DESCRIPTION

Multiple purpose versatile etching tool for WBG materials and metal etching.

### RESEARCH SERVICES

R&D versatile capability etching Tool with wide temperature range heated lower electrode. Proposed for wide band gap materials, glass and ceramics Dry etching. Mechanical clamping for wafers up to 8" in diameter.

### METHODS & EXPERTISE ON THE RESEARCH INFRASTRUCTURE

Material etching portfolio:

- Metals
- PZT
- AlN and AlScN (up to 40% Scandium)
- LiNbO
- SiC, SiOC
- GaN, InGaN, AlGaIn

### CONTACT

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